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<table style="width: 100%; border: none;"> <tr> <td style="width: 50%; vertical-align: top; padding: 5px;"> (21) International Application Number: PCT/EP99/04234 (22) International Filing Date: 18 June 1999 (18.06.99) (30) Priority Data: 98810596.1 26 June 1998 (26.06.98) EP (71) Applicant (for all designated States except US): CIBA SPECIALTY CHEMICALS HOLDING INC. [CH/CH]; Klybeckstrasse 141, CH-4057 Basel (CH). (72) Inventors; and (75) Inventors/Applicants (for US only): OKA, Hidetaka [JP/JP]; 18-27, Suenari-cho, Takarazuka, Hyogo 665 (JP). OHWA, Masaki [JP/JP]; 1-1-4, Kotoku-cho, Nada-ku, Kobe City 657 (JP). MATSUMOTO, Akira [JP/JP]; B-102, 56, Higashiura-machi, Ichijyoji, Sakyo-ku, Kyoto City 606 (JP). KURA, Hisatoshi [JP/JP]; 5-3-15-205, Obayashi, Takarazuka, Hyogo 665 (JP). (74) Common Representative: CIBA SPECIALTY CHEMICALS HOLDING INC.; Patentabteilung, Klybeckstrasse 141, CH-4057 Basel (CH). </td> <td style="width: 50%; vertical-align: top; padding: 5px;"> (81) Designated States: AE, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CU, CZ, DE, DK, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, UA, UG, US, UZ, VN, YU, ZA, ZW, ARIPO patent (GH, GM, KE, LS, MW, SD, SL, SZ, UG, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG). Published <i>With international search report.</i> <i>Before the expiration of the time limit for amending the claims and to be republished in the event of the receipt of amendments.</i> </td> </tr> </table>			(21) International Application Number: PCT/EP99/04234 (22) International Filing Date: 18 June 1999 (18.06.99) (30) Priority Data: 98810596.1 26 June 1998 (26.06.98) EP (71) Applicant (for all designated States except US): CIBA SPECIALTY CHEMICALS HOLDING INC. [CH/CH]; Klybeckstrasse 141, CH-4057 Basel (CH). (72) Inventors; and (75) Inventors/Applicants (for US only): OKA, Hidetaka [JP/JP]; 18-27, Suenari-cho, Takarazuka, Hyogo 665 (JP). OHWA, Masaki [JP/JP]; 1-1-4, Kotoku-cho, Nada-ku, Kobe City 657 (JP). MATSUMOTO, Akira [JP/JP]; B-102, 56, Higashiura-machi, Ichijyoji, Sakyo-ku, Kyoto City 606 (JP). KURA, Hisatoshi [JP/JP]; 5-3-15-205, Obayashi, Takarazuka, Hyogo 665 (JP). (74) Common Representative: CIBA SPECIALTY CHEMICALS HOLDING INC.; Patentabteilung, Klybeckstrasse 141, CH-4057 Basel (CH).	(81) Designated States: AE, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CU, CZ, DE, DK, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, UA, UG, US, UZ, VN, YU, ZA, ZW, ARIPO patent (GH, GM, KE, LS, MW, SD, SL, SZ, UG, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG). Published <i>With international search report.</i> <i>Before the expiration of the time limit for amending the claims and to be republished in the event of the receipt of amendments.</i>
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(54) Title: PHOTOPOLYMERIZABLE THERMOSETTING RESIN COMPOSITIONS				
(57) Abstract Compositions comprising (A) an oligomer or polymer containing at least one carboxylic acid group in the molecule; (B) at least one compound of formulas (I, II, III, IV, V or VI), wherein R₁ inter alia is phenyl or alkyl; R₂ is for example C₂-C₁₂alkanoyl which is unsubstituted or substituted or is benzoyl; R₃, R₄, R₅, R₆ and R₇ independently of one another are for instance hydrogen, C₁-C₁₂alkyl, cyclohexyl or phenyl which is unsubstituted or substituted, or are benzyl, benzoyl, C₂-C₁₂alkanoyl or phenoxycarbonyl; R₈ is for example hydrogen or C₁-C₁₂alkyl or a group (B); M is for example C₁-C₁₂alkylene, cyclohexylene or phenylene; M₁ inter alia is a direct bond or C₁-C₁₂alkylenoxy; and Ar is a 5- or 6-membered aromatic heterocyclic ring; (C) a photopolymerizable reactive or unreactive diluent; and (D) as a thermosetting component an epoxy compound containing at least two epoxy groups in one molecule; are highly suitable as resists which are alkaline developable.				